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1R. Sudo, 2T. Ito, 2M. Yasui, 2S. Kaneko
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Annealing of the Al_{3.15}Sc_{2.37} Co-Doped ZnO Sputtered Film Under Oxygen Atmosphere

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Microstructure and Characterization of Al, Sc Co-Doped ZnO Sputtered Thin Film

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K. Sakamoto, A. Komura, H. Hoshino, Y. Takemura
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Y. T. Liao, J. G. Duh
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¹S. M. Lin, ²T. J. Hsueh, ³H. C. C. Lu, ²S. Y. Lin, ²J. Y. Tsai, ¹S. C. Chen
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The Effect of Gas Blowing to Substrate on Microwave-Assisted High-Speed DLC Coating

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C. H. Chao, K. Y. Peng, D. H. Wei
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¹P. W. Chi, ¹C. W. Su, ¹B.H. Jhuo, ²Y. C. Yu, ²Y. D. Yao, ¹D. H. Wei
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¹M. Noma, ²K. Eriguchi, ³S. Hasegawa, ⁴M. Yamashita, ²Y. Takao, ¹N. Terayama, ²K. Ono
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¹K. Y. Peng, ³Y. W. Chen, ¹C. H. Chao, ³H. J. Sheen, ²P. K. Wei, ¹D. H. Wei
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¹Y. Lu, ¹K. Makihara, ¹D. Takeuchi, ²K. Sakaike, ²M. Akazawa, ²S. Higashi, ¹S. Miyazaki
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¹M. J. Rahman, ^{1,2}T. Mieno
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¹H. Iwata, ²M. Takagi, ¹Y. Tokuda
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¹H. Z. Chen, ¹M. C. Kao, ¹S. L. Young, ²C. Y. Kung
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¹E. M. Fujiwara, ²A. Obata, ²Y. Watanabe, ²T. Kasuga, ³M. Niinomi, ¹T. Yamasaki
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¹H.H. Yu, ¹C.K Huang, ¹H.Y. Wen, ²K.Y. Cheng, ¹M.Y.Chang
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